- 1. A uniformly doped silicon npn bipolar transistor is to be biased in the forward-active mode with the B-C junction reverse biased by 3v. The metallurgical base width is 1.10 μ m. The transistor dopings are $N_E = 10^{17}$ cm⁻³, $N_B = 10^{16}$ cm⁻³, and $N_c = 10^{15}$ cm⁻³. (a) For T = 300 K, calculate the B-E voltage at which the minority carrier electron concentration at x = 0 is 10 percent of the majority carrier hole concentration. (b) At this bias, determine the minority carrier hole concentration at x'= 0. (c) Determine the neutral base width for this bias.
- 2. A silicon npn bipolar transistor is uniformly doped and biased in the forward-active region. The neutral base width is $x_B = 0.8 \ \mu m$. The transistor doping concentrations are $N_E = 5 \times 10^{17} \text{ cm}^{-3}$, $N_B = 10^{16} \text{ cm}^{-3}$, and $N_c = 10^{15} \text{ cm}^{-3}$. (a) Calculate the values of p_{E0} , n_{B0} . and p_{C0} . (b) For $V_{BE} = 0.625$ V, determine n_B at x=0 and p_E at x' = 0. (c) Sketch the minority carrier concentrations through the device and label each curve.
- 3. Consider a uniformly doped npn bipolar transistor at T = 300 K with the following parameters:

$N_E = 10^{18} \text{ cm}^{-3}$	$N_B = 5 \times 10^{16} \text{ cm}^{-3}$	$N_c = 10^{15} \text{ cm}^{-3}$
$D_E = 8 \text{ cm}^2/\text{s}$	$D_B = 15 \text{ cm}^2/\text{s}$	$D_C = 12 \text{ cm}^2/\text{s}$
$\tau_{E0} = 10^{-8} \text{ s}$	$\tau_{B0} = 5 \times 10^{-8} \text{ s}$	$\tau_{C0} = 10^{-8} \text{ s}$
$x_E = 0.8 \ \mu \mathrm{m}$	$x_B = 0.7 \ \mu \mathrm{m}$	

Drive equation for J_{Ep} considering x_E . For $V_{BE} = 0.60$ V and $V_{CE} = 5$ V, calculate (*a*) the currents J_{Ep} , J_{En} , and J_{Cn} (*b*) the current gain factors γ , α_T , α , and β .

4. Three npn bipolar transistors have identical parameters except for the base doping concentrations and neutral base widths. The base parameters for the three devices are as follows:

Device	Base doping	Base width
А	$N_B = N_{B0}$	$x_B = x_{B0}$
В	$N_B = 2N_{B0}$	$x_B = x_{BO}$
С	$N_B = N_{B0}$	$x_B = 0.5 x_{B0}$

(The base doping concentration for the B device is twice that of A and C, and the neutral base width for the C device is half that of A and B.)

(*a*) Determine the ratio of the emitter injection efficiency of (*i*) device B to device A and (*ii*) device C to device A.

(*b*) Repeat part (*a*) for the base transport factor.

(c) Which device has the largest common-emitter current gain β ?

5. The symmetrical p^+-n-p^+ transistor is connected as a diode in the four configurations shown. Assume that V >> kT/q. Sketch $\delta p(x_n)$ in the base region for each case. Which connection seems most appropriate for use as a diode? Why?



6. The base doping in a diffused n⁺-p-n bipolar transistor can be approximated by an exponential

$$N_B = N_B(0)exp\left(-ax/x_B\right)$$

where *a* is a constant and is given by

$$a = \ln \left(N_B(0) / N_B(x_B) \right)$$

(a) Show that, in thermal equilibrium, the electric field in the neutral base region is a constant.

(*b*) Indicate the direction of the electric field. Does this electric field aid or retard the flow of minority carrier electrons across the base?

(c) Derive an expression for the steady-state minority carrier electron concentration in the base under forward bias. Assume no recombination occurs in the base. (Express the electron concentration in terms of the electron current density.)